

# INFORMATION DISCLOSURE CITATION

(Use several sheets if necessary)

Docket Number (Optional)

FIS920000237 (00750430AA)

Application Number

09/809,766

Applicant(s)

Ferrera et al.

Filing Date

03/15/2001

Group Art Unit

2881

## U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE

## FOREIGN PATENT DOCUMENTS

	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
							YES	NO

## OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

P6		Goodberlet et al.; "A One-Dimensional Demonstration of Spatial-Phase-Locked Electron-Beam Lithography"; Elsevier Science B.V. - Microelectronic Engineering; 1997; pgs. 473-476
P6		Goodberlet et al.; "Extending Spatial-Phase-Locked Electron Beam Lithography to Two Dimensions"; Jpn. J. Appl. Phys., Vol. 36, Pt. 1, No. 12B; 1997; pgs. 7557-7559

EXAMINER	Paul Guzzo	DATE CONSIDERED	7/30/04
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EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.